

CHEMICAL
VAPOR
DEPOSITION

Principles and Applications

edited by

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Contents

Contributors	vii
Foreword	ix
1. Chemical Vapor Deposition—An Overview	
<i>Michael L. Hitchman and Klavs F. Jensen</i>	1
1.1 Introduction	1
1.2 CVD processes	3
1.3 Layers grown by CVD	16
1.4 Applications of CVD	25
1.5 Future trends	25
References	26
2. Fundamentals of Chemical Vapor Deposition	
<i>Klavs F. Jensen</i>	31
2.1 Introduction	31
2.2 CVD reactor systems	32
2.3 Nucleation and growth	35
2.4 Chemical reaction mechanisms and kinetics	39
2.5 Transport phenomena	50
2.6 CVD models	66
2.7 Summary	83
References	84
3. Analysis of Chemical Vapor Deposition Processes	
<i>William G. Breiland and Pauline Ho</i>	91
3.1 Introduction	91
3.2 Fluid mechanics diagnostics	92
3.3 Gas-phase chemical species measurements	111
3.4 Analysis of particles	147
3.5 Conclusions	150
References	150
4. Chemical Vapor Deposition at Low Pressures	
<i>Michael L. Hitchman and Klavs F. Jensen</i>	159
4.1 Introduction	159
4.2 Models of LPCVD reactors	162

4.3	Polycrystalline silicon	183
4.4	Summary	215
	References	215
5.	Silicon Epitaxy by Chemical Vapor Deposition <i>Bernard S. Meyerson</i>	219
5.1	Introduction	219
5.2	Conventional silicon epitaxy	220
5.3	Low temperature epitaxy	227
5.4	Devices	238
5.5	Conclusions	242
	References	242
6.	Organometallic Vapor Phase Epitaxy of III-V Materials <i>R.L. Moon and Yu-Min Houng</i>	245
6.1	Introduction	245
6.2	Growth process	255
6.3	Growth of III-V materials	289
6.4	Growth of quantum well structures (ultrathin layers)	328
6.5	Selective area growth	344
6.6	Atomic layer epitaxy and vacuum OMVPE	354
6.7	Growth for production	360
6.8	Monitoring OMVPE growth	367
6.9	Summary and future trends	371
	Acknowledgment	373
	References	373
	Appendices	381
7.	Plasma-Assisted Chemical Vapor Deposition <i>Dennis W. Hess and David B. Graves</i>	385
7.1	Introduction	385
7.2	Fundamentals	386
7.3	Modeling	402
7.4	Specific film materials	420
	References	431
8.	Photo-Assisted Chemical Vapor Deposition <i>V.R. McCrary and V.M. Donnelly</i>	437
8.1	Introduction	437
8.2	Experimental techniques	448
8.3	Fundamental processes	458
8.4	Photodeposited materials	490

8.5	Conclusions	505
	Acknowledgment	506
	References	506
9.	Electronic and Optical Characterization of Chemical Vapor Deposition Films for Device Applications	
	<i>W.B. Jackson</i>	515
9.1	Introduction	515
9.2	Optical characterization	517
9.3	Electron spin resonance	532
9.4	Electrical characterization techniques	541
9.5	Characterization using specific devices	570
9.6	Conclusions	586
	References	587
10.	Protective Coatings	
	<i>G. Wahl</i>	591
10.1	Introduction	591
10.2	General considerations	592
10.3	Applications	631
10.4	Low-temperature deposition	651
	References	656
	Index	663